(12) INTERNATIONAL APPLICATION PUBLISHED UNDER THE PATENT COOPERATION TREATY (PCT)

(19) World Intellectual Property Organization
International Bureau

(43) International Publication Date
6 May 2010 (06.05.2010)

PCT

(10) International Publication Number
WO 2010/051174 A1

(51) International Patent Classification:
B01D 53/68 (2006.01) ***C23G 5/028*** (2006.01)
B23P 6/00 (2006.01) ***F01D 25/00*** (2006.01)

(21) International Application Number:
PCT/US2009/061120

(22) International Filing Date:
19 October 2009 (19.10.2009)

(25) Filing Language: English

(26) Publication Language: English

(30) Priority Data:
12/262,779 31 October 2008 (31.10.2008) US

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(81) Designated States *(unless otherwise indicated, for every kind of national protection available)*: AE, AG, AL, AM, AO, AT, AU, AZ, BA, BB, BG, BH, BR, BW, BY, BZ, CA, CH, CL, CN, CO, CR, CU, CZ, DE, DK, DM, DO, DZ, EC, EE, EG, ES, FI, GB, GD, GE, GH, GM, GT, HN, HR, HU, ID, IL, IN, IS, JP, KE, KG, KM, KN, KP, KR, KZ, LA, LC, LK, LR, LS, LT, LU, LY, MA, MD, ME, MG, MK, MN, MW, MX, MY, MZ, NA, NG, NI, NO, NZ, OM, PE, PG, PH, PL, PT, RO, RS, RU, SC, SD, SE, SG, SK, SL, SM, ST, SV, SY, TJ, TM, TN, TR, TT, TZ, UA, UG, US, UZ, VC, VN, ZA, ZM, ZW.

(84) Designated States *(unless otherwise indicated, for every kind of regional protection available)*: ARIPO (BW, GH, GM, KE, LS, MW, MZ, NA, SD, SL, SZ, TZ, UG, ZM, ZW), Eurasian (AM, AZ, BY, KG, KZ, MD, RU, TJ, TM), European (AT, BE, BG, CH, CY, CZ, DE, DK, EE, ES, FI, FR, GB, GR, HR, HU, IE, IS, IT, LT, LU, LV, MC, MK, MT, NL, NO, PL, PT, RO, SE, SI, SK, SM, TR), OAPI (BF, BJ, CF, CG, CI, CM, GA, GN, GQ, GW, ML, MR, NE, SN, TD, TG).

Published:

— *with international search report (Art. 21(3))*

(54) Title: SYSTEM AND APPARATUS FOR FLUORIDE ION CLEANING

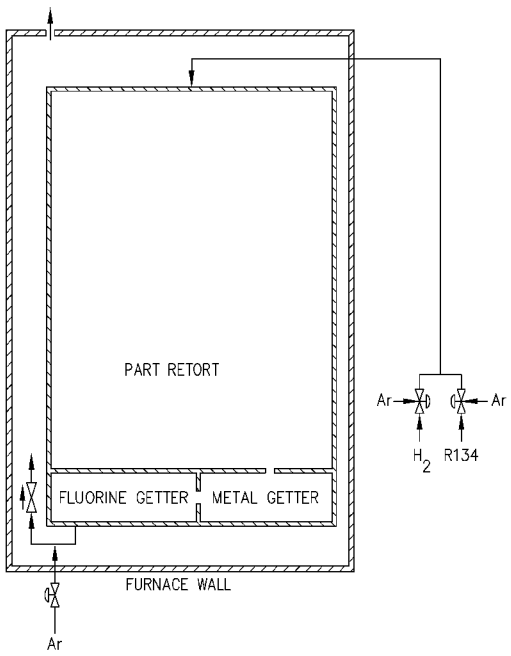


FIG. 1

(57) Abstract: System and apparatuses for utilizing in-situ generated hydrogen fluoride (HF) in a cleaning process. An exemplar)1 system includes a cleaning retort operable at a temperature sufficient to promote an in-situ reaction between a liquid or gaseous haJogenated feedstock and hydrogen gas to form the HF, The system includes a liquid or gaseous halogenated feedstock source and a hydrogen gas source disposed outside the cleaning retort which, upon reaction generate the HF within the cleaning retort. A HF scrubber, disposed within the cleaning retort, is operable to substantially remove residual HF gas formed by the in-situ reaction. An exemplary apparatus includes a cleaning retort having a first region able to hold parts in need of cleaning and a second region operable as a HF scrubber.

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